

The NEW JCM-6000 NeoScope™

A desktop scanning electron microscope

High performance system in a compact, innovative model.

- Intuitive touch panel operation with new GUI
- Well focused 3D morphological observation
- Backscattered electron imaging for compositional distribution
- Metrology supported
- Imaging of tilted, rotated samples* (optional)



*Tilt/rotation motor drive holder included

- **Resolution and Analytical Performance:**
Superior technology – magnification range: from $\times 10$ to $\times 60,000$.
Optional EDS for elemental analysis
- **Simple to use and maintenance:**
Intuitive software combined with a Multi-touch display Automated alignment and image adjustment Simple and quick sample exchange Easy filament replacement
- **Excellent affordable:**
Affordable imaging tool for high resolution and depth of field
Space-saving design
Ideal for multiple users from novice to expert
- **Features:**
Both high-vacuum and low-vacuum imaging modes
Both Secondary and Backscattered Electron imaging
Feature measurement
Specimen tilt and rotation
Analytical capability with optional EDS system



JEOL

For more information please contact

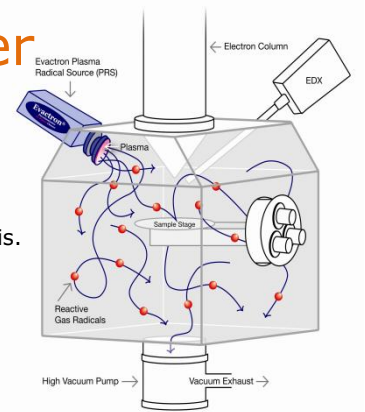
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AVBA

The Evactron[®] RF plasma cleaner

Improves electron microscope imaging and analytical performance by removing contamination. It cleans and breaks down oils and other hydrocarbons in most vacuum chambers resulting in high-quality images and carbon-free analysis. It can be used as an *in-situ* solution, cleaning EUV and X-ray optics.



In the Evactron Plasma, oxygen radicals are created. Then, they flow through the chamber from the Evactron Plasma to the pump port. The radicals chemically etch *inside the chamber* any hydrocarbon contamination they encounter. The reaction products are CO, CO₂, and H₂O, which are then pumped out of the system.

Evactron[®] CombiClean[™] Chamber

The Evactron CombiClean system combines onboard vacuum cleaning chamber and external PRS (Plasma Radical Source) control in one unified system.



Controls multiple Plasma Radical Sources with simple front panel switch.
Cleans samples as well as chambers

Evactron[®] TEM wand

The RF electrode used to create the oxygen radicals is now mounted on the end of a TEM sample rod. The user first vents the chamber and then inserts the Wand similar to the way one would insert a sample rod. Now cleaning in the TEM can occur right where it is needed in the sample examination region



Insert into TEM chamber just like a sample rod.

Cleans critical area around the pole pieces



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